

Abstract

A pattern forming method is provided for forming film patterns W1 to W3 by arranging droplets of a liquid material on a substrate. The method comprises the steps of: defining a plurality of pattern forming areas R1 to R3 in which the film patterns should be formed on the substrate; and sequentially arranging a plurality of droplets in the plurality of defined pattern forming areas R1 to R3, thereby forming the film patterns W1 to W3, wherein the droplets are sequentially arranged by setting an arrangement order of the droplets to be substantially equal for the plurality of pattern forming areas R1 to R3.